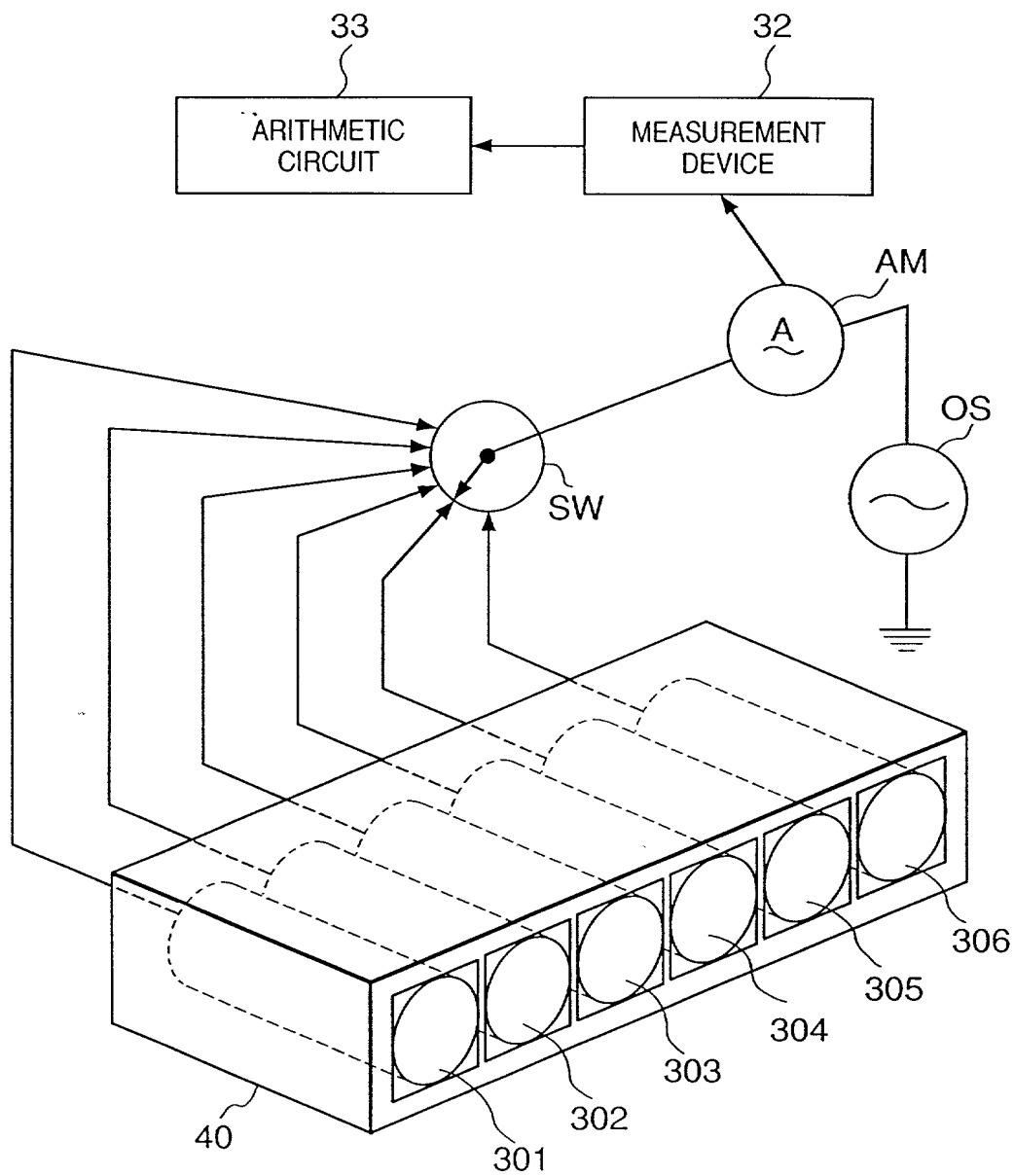


FIG. 1



20161014625001



FIG. 3

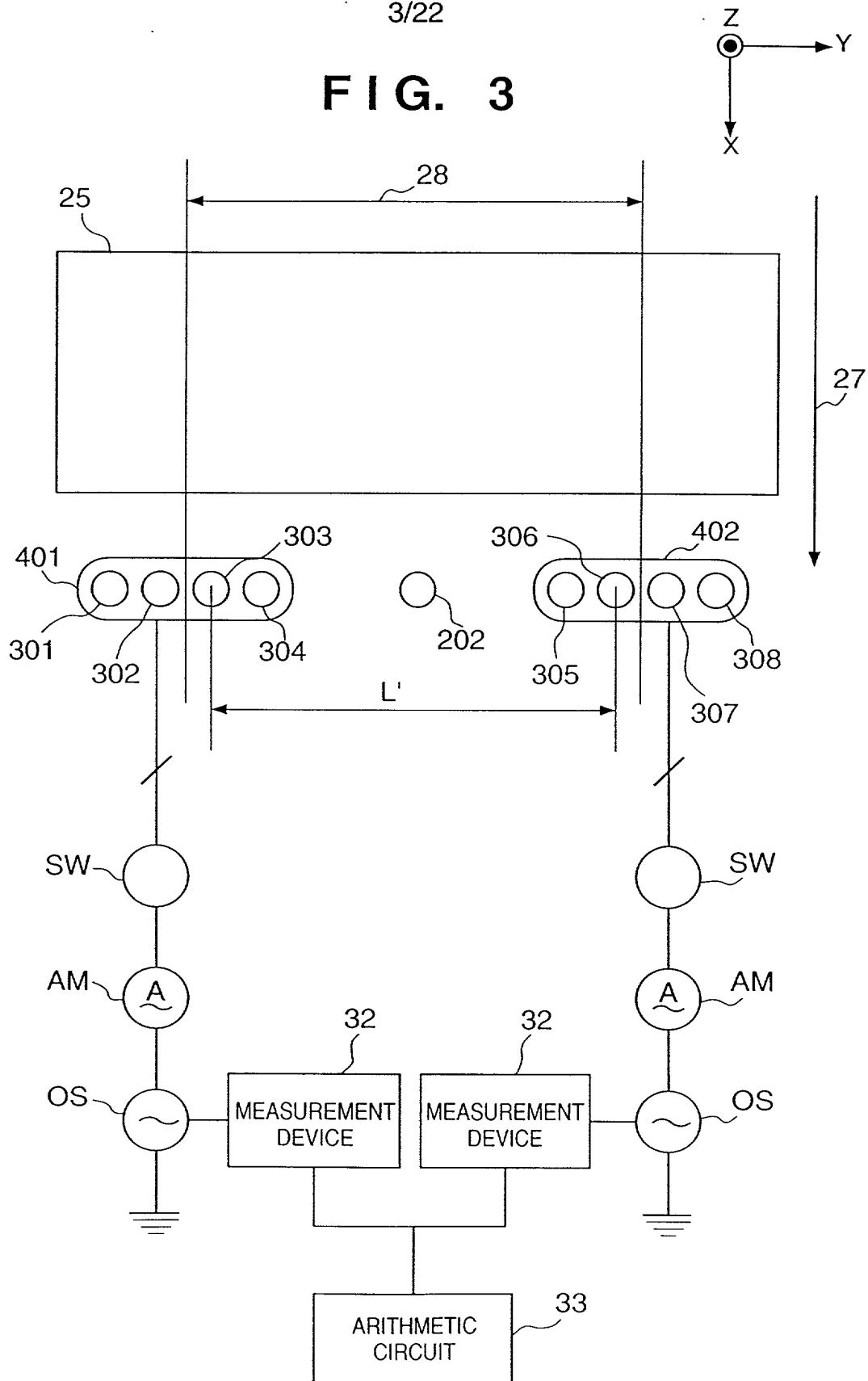


FIG. 4

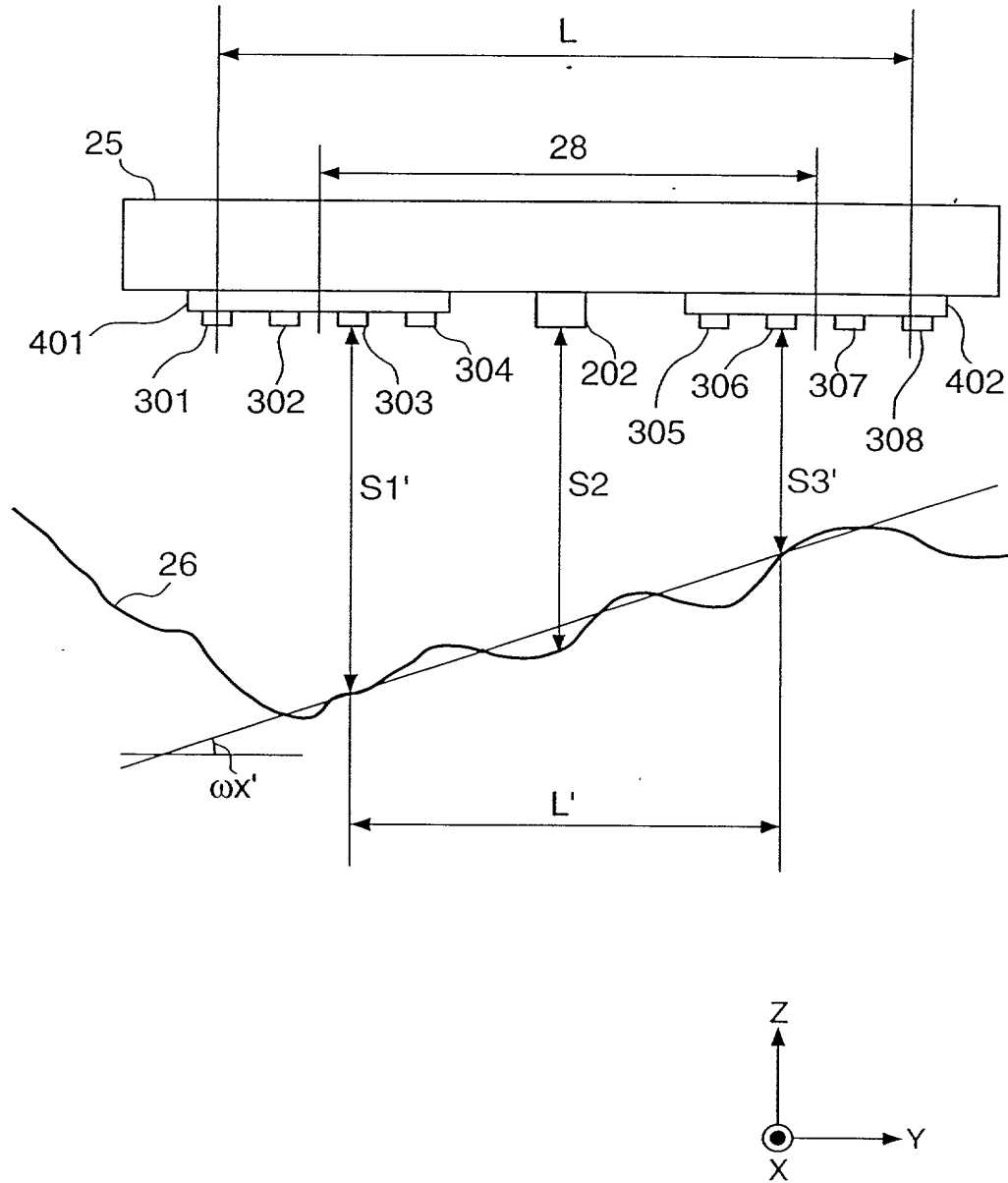


FIG. 5

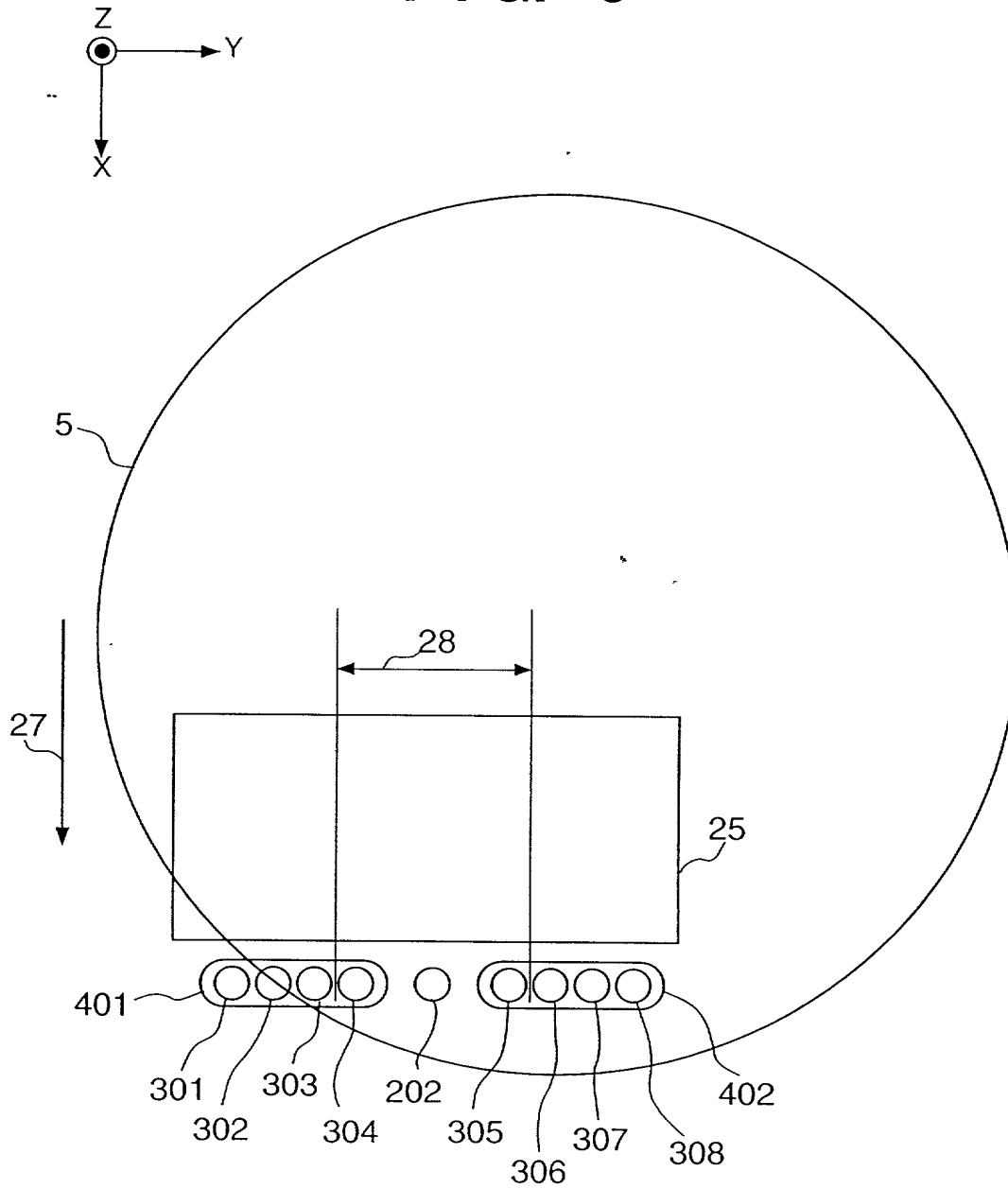


FIG. 6

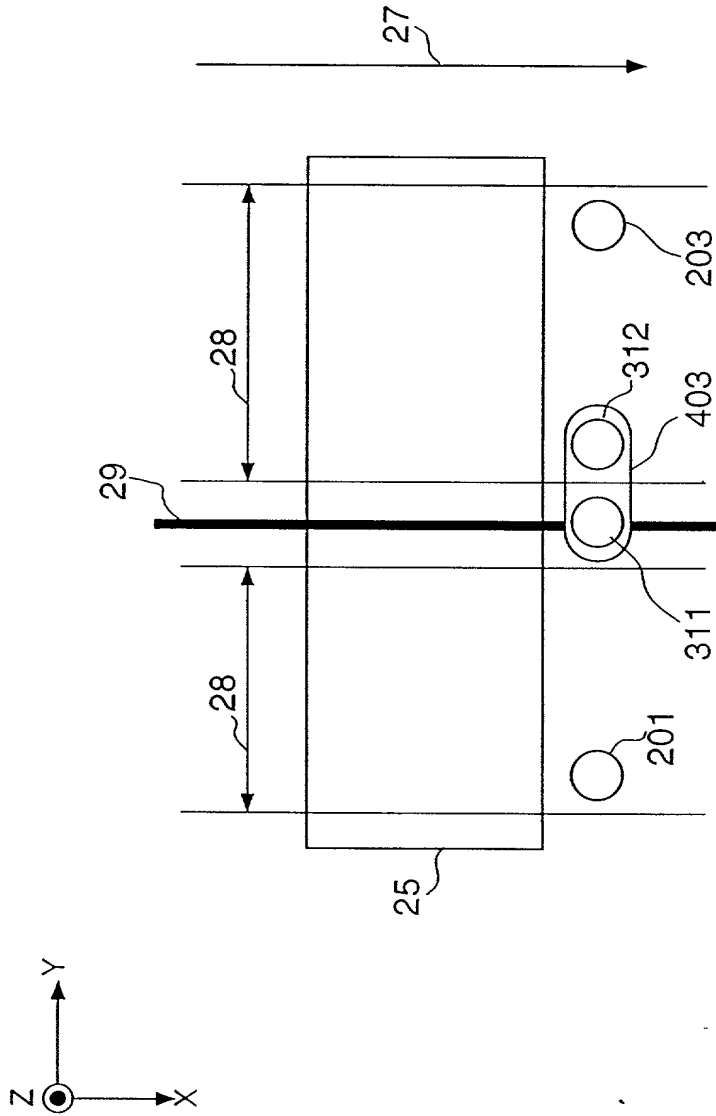


FIG. 7

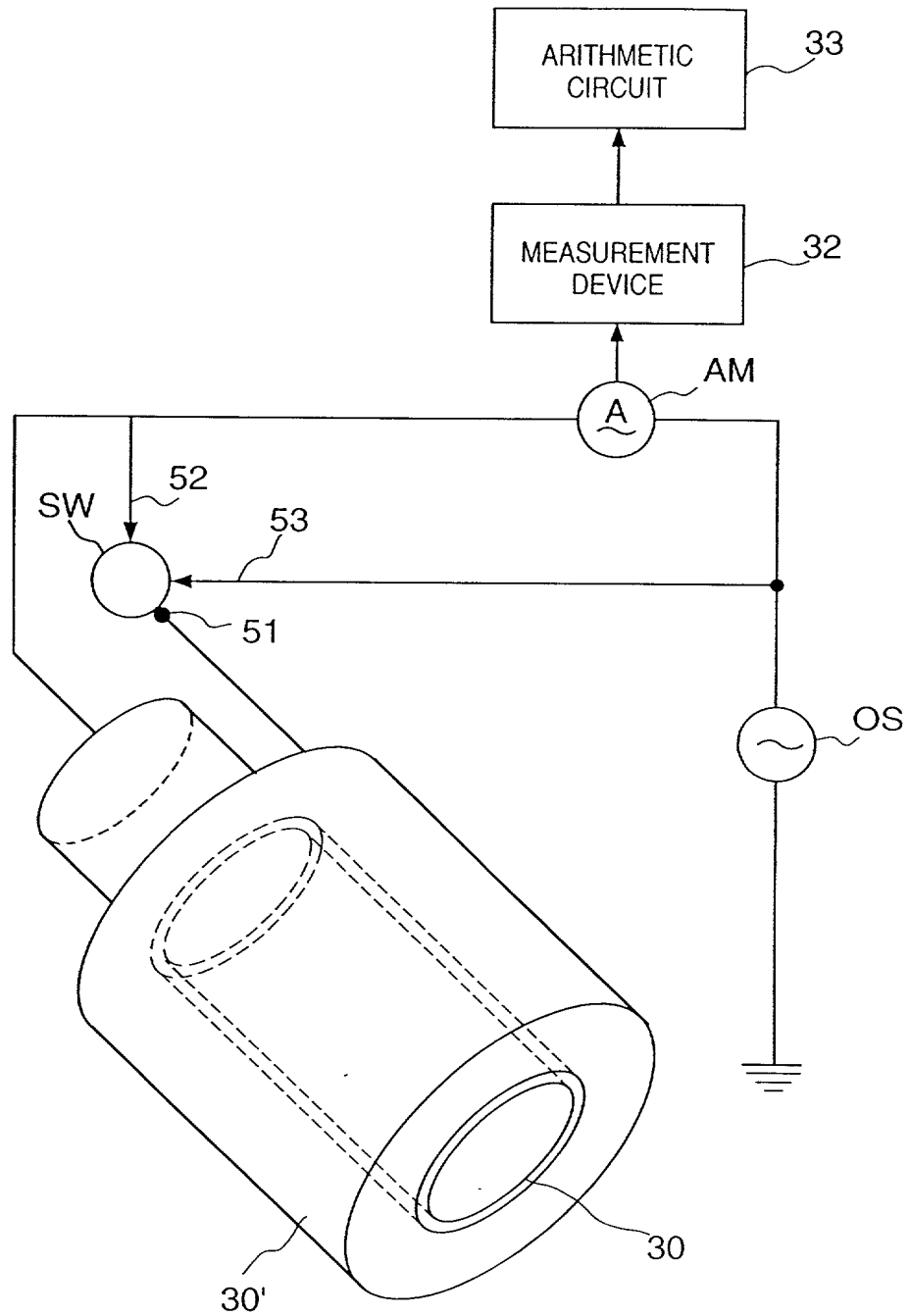


FIG. 8

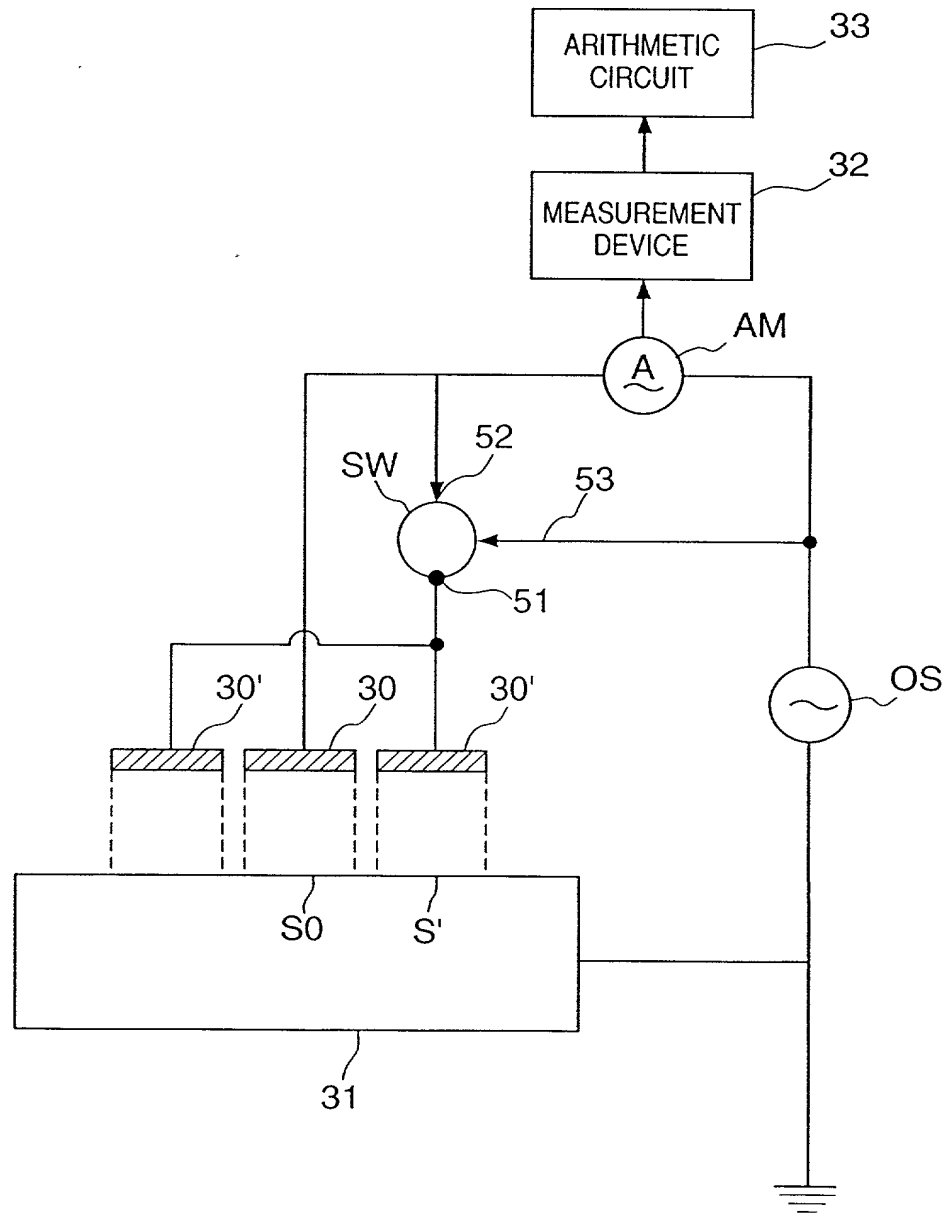




FIG. 9

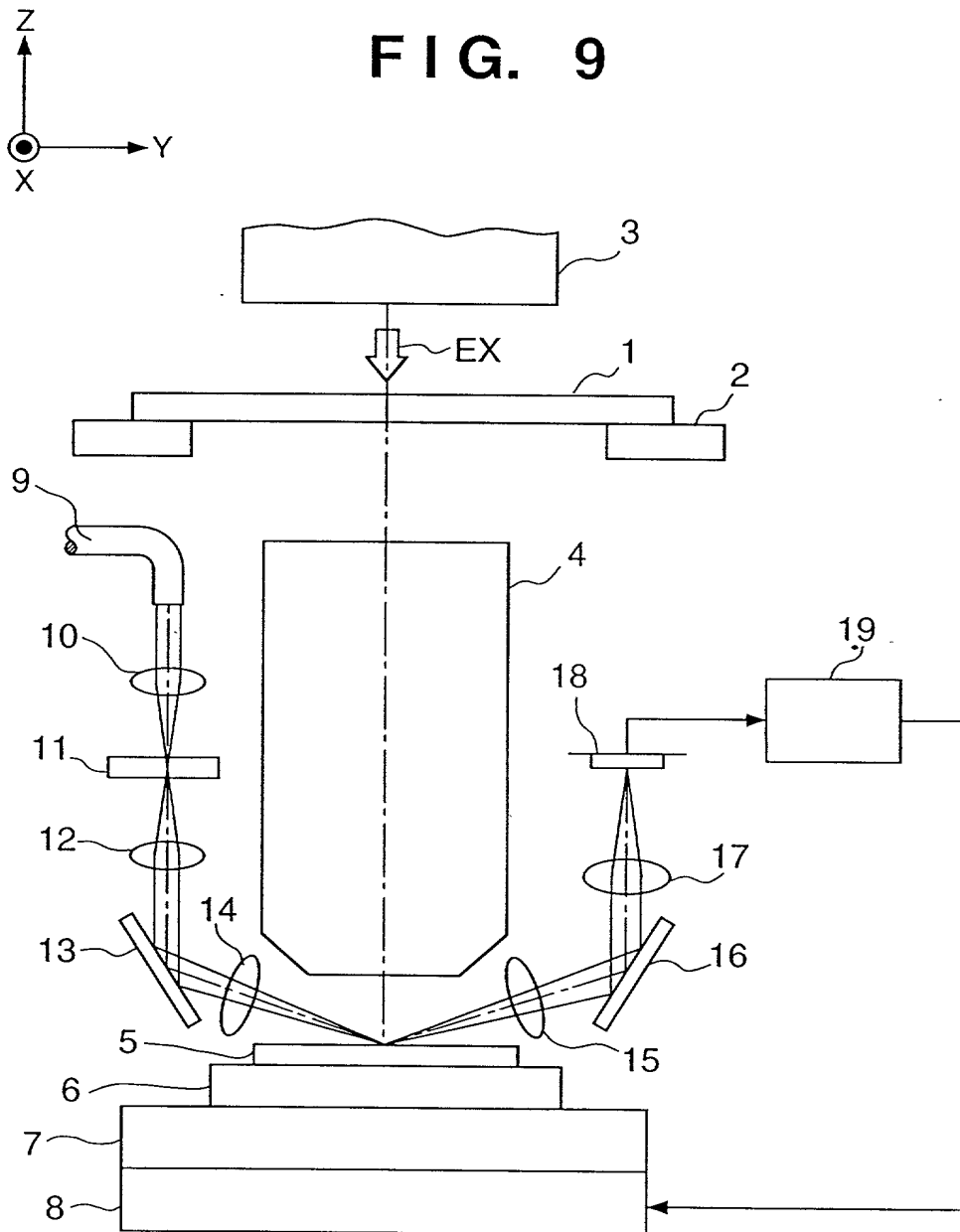


FIG. 10

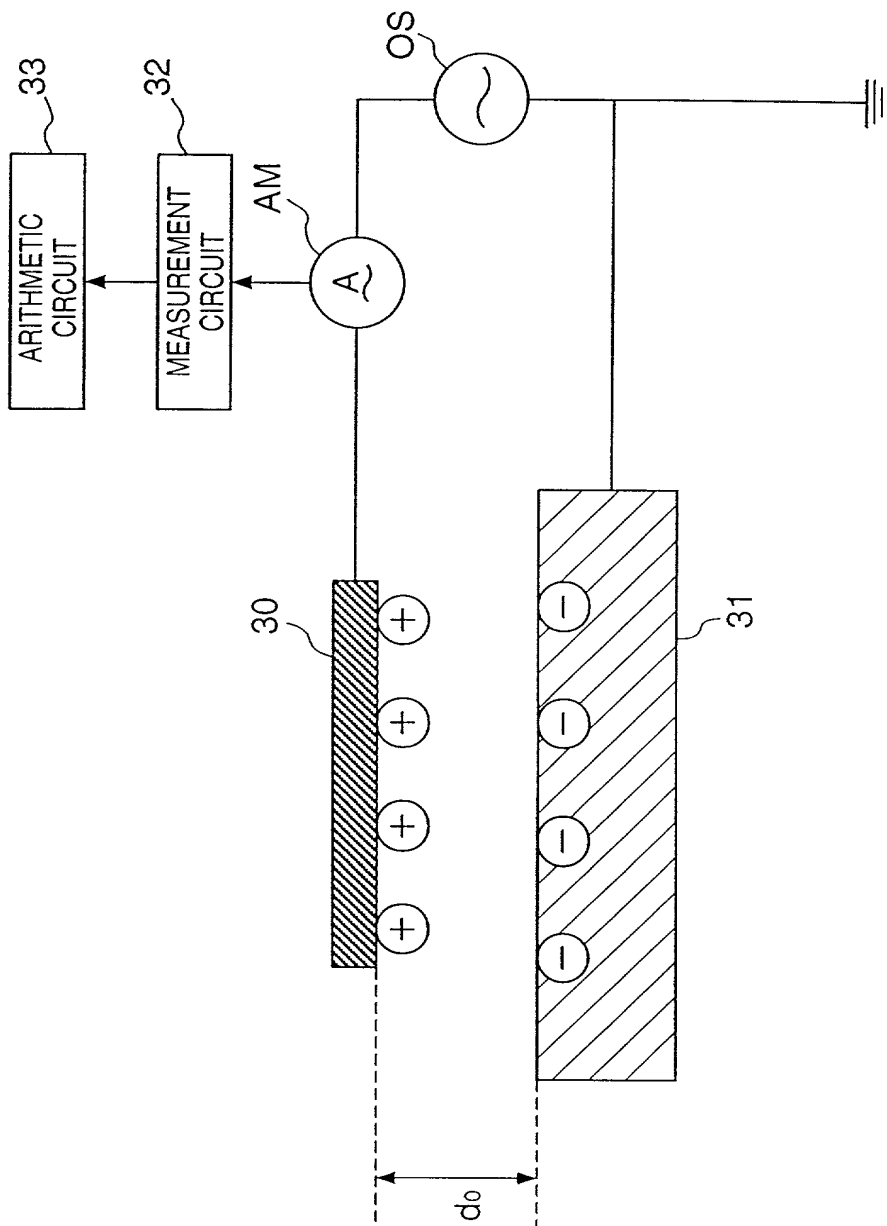


FIG. 11

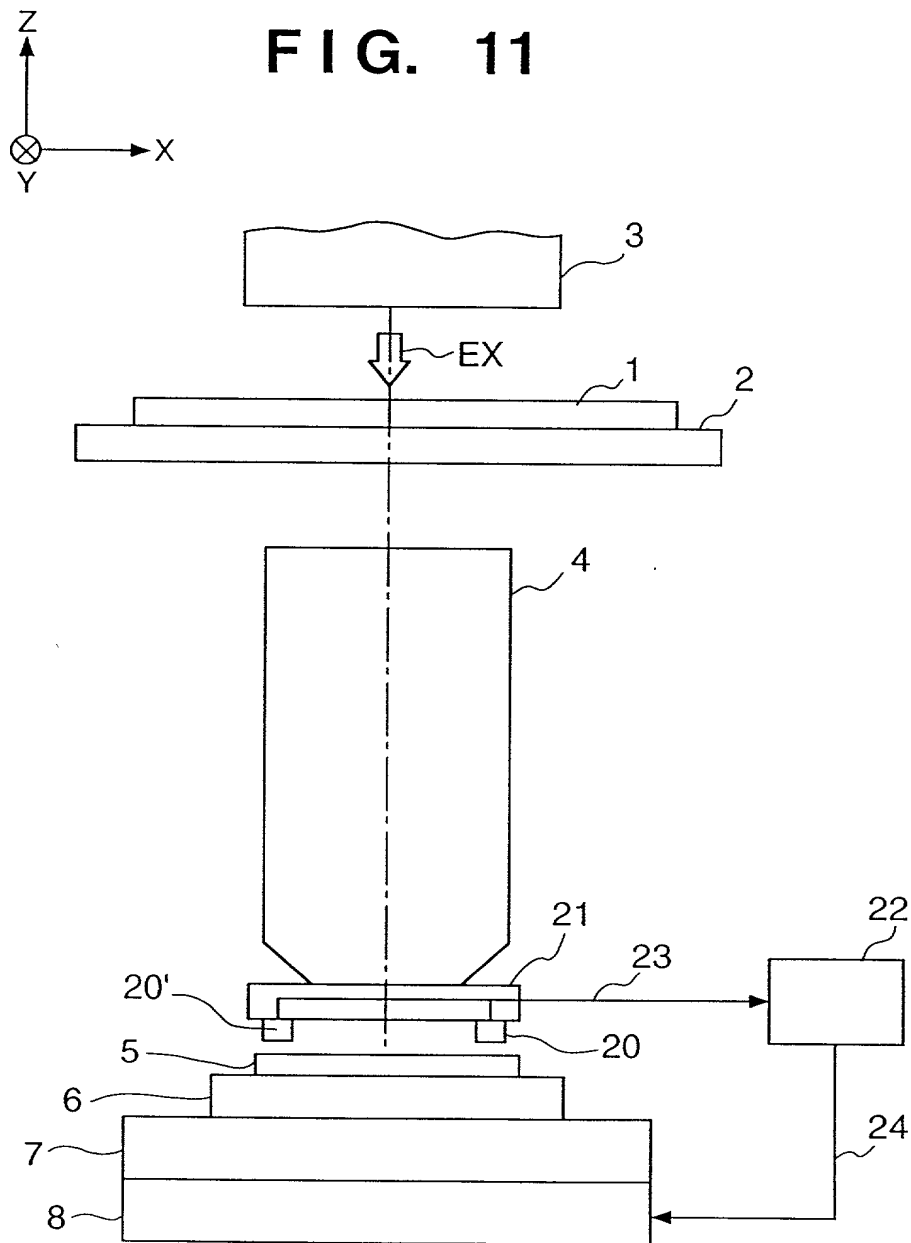


FIG. 12

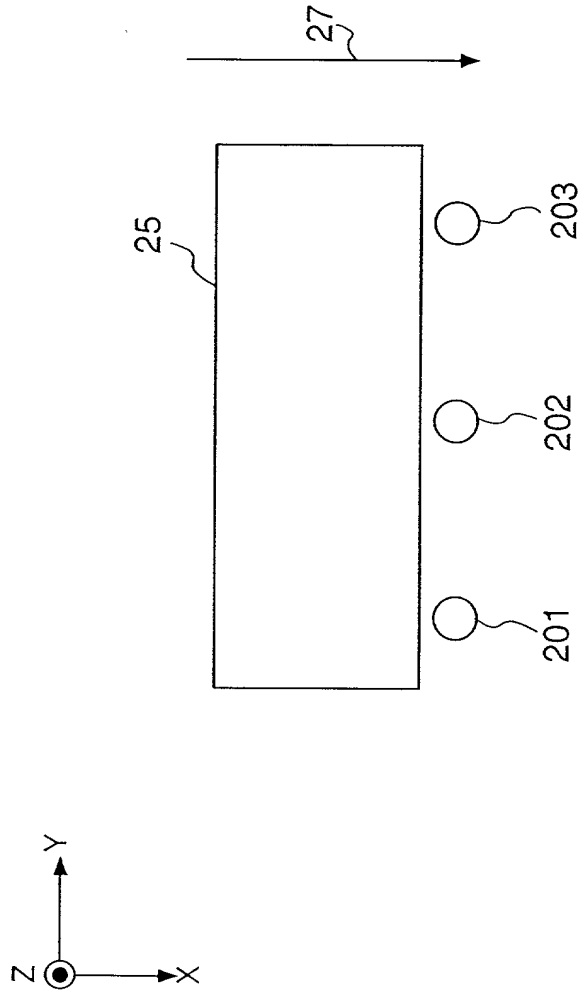


FIG. 13

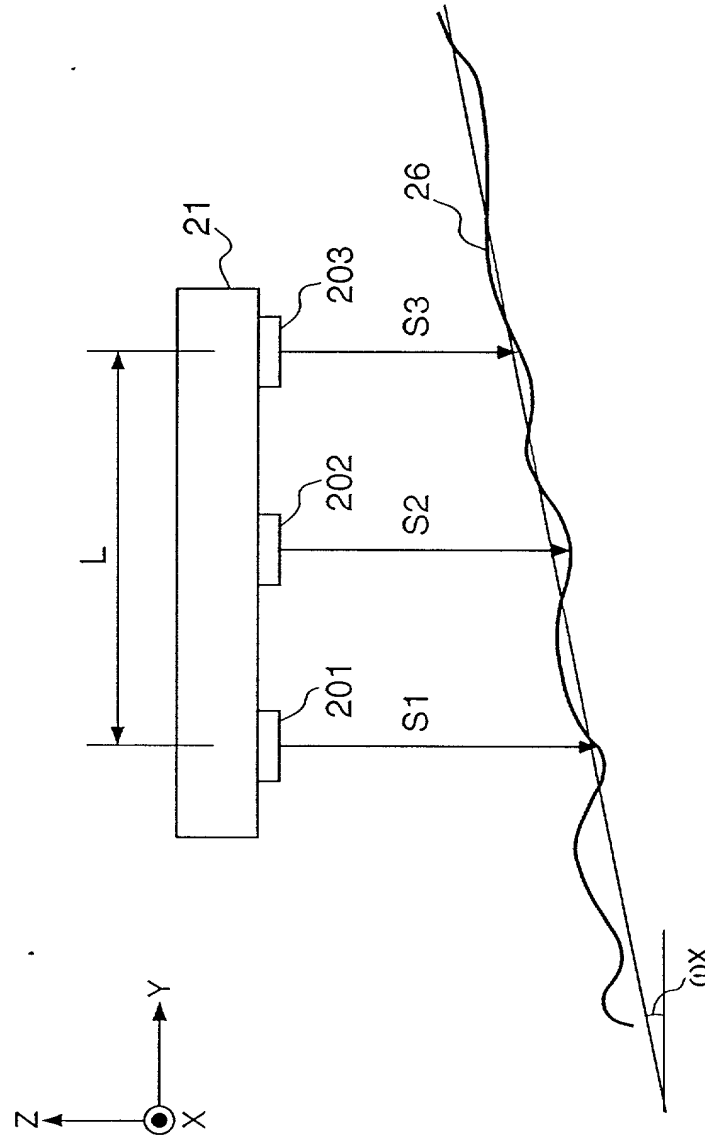


FIG. 14

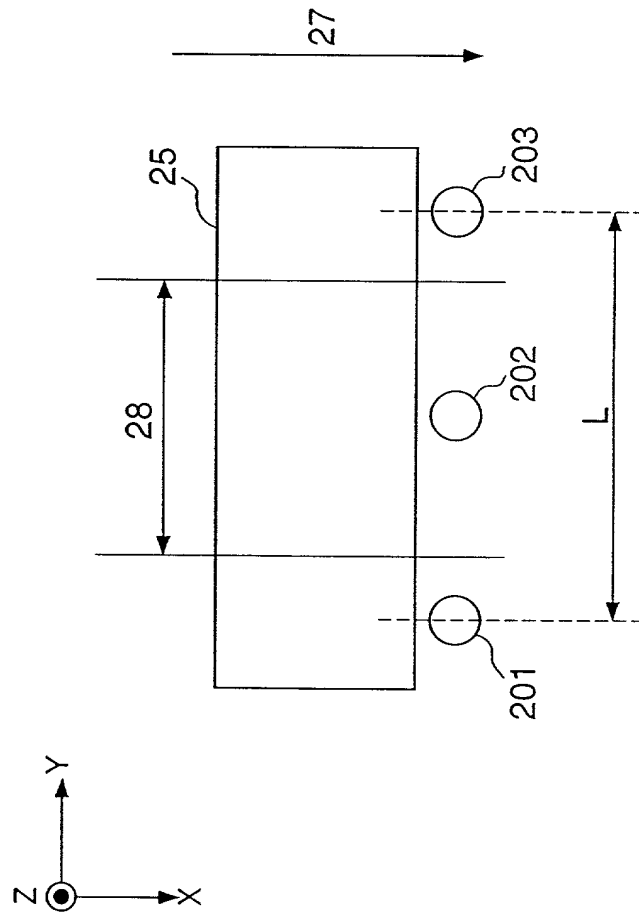
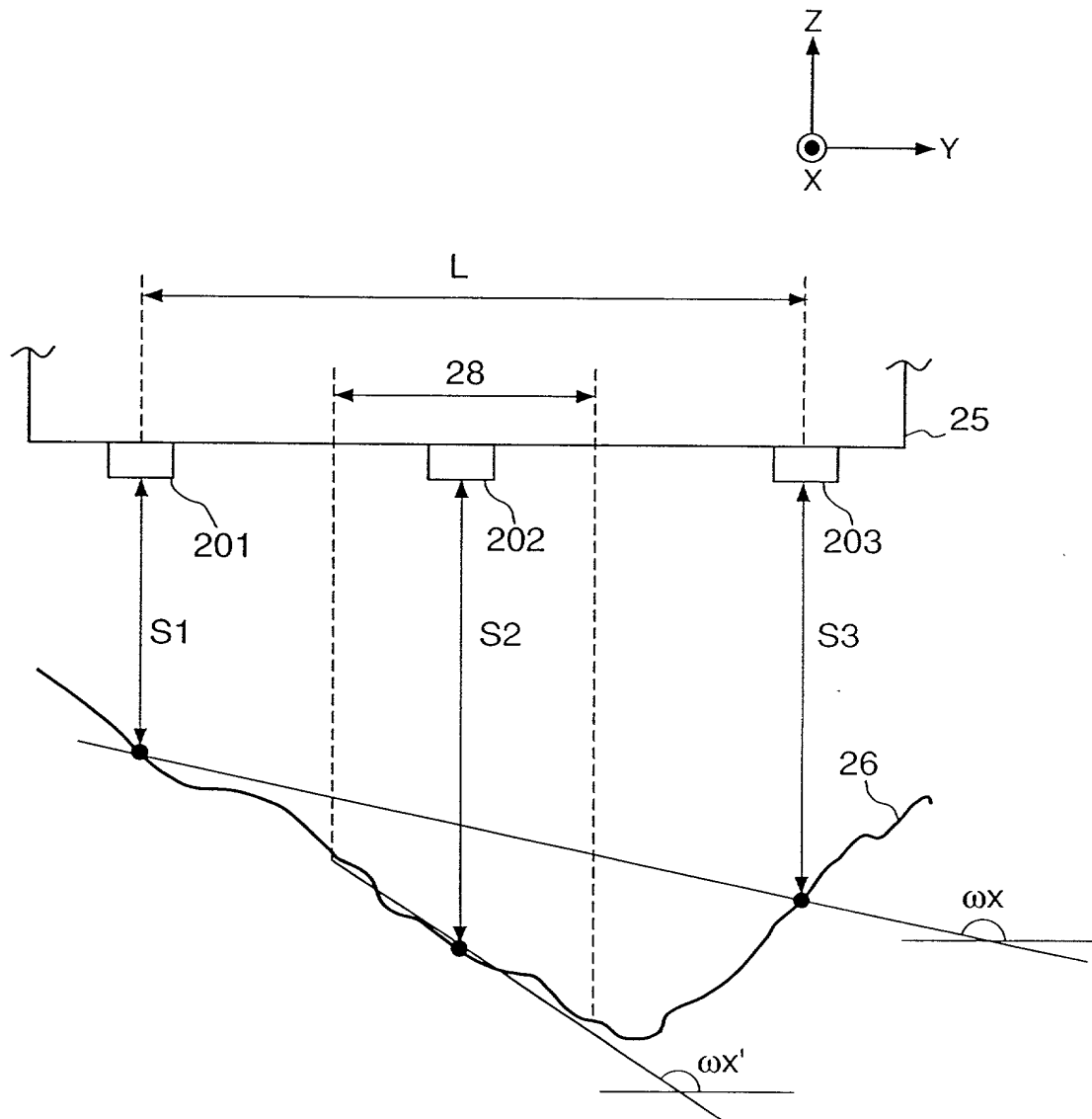


FIG. 15



201E10-46265001

FIG. 16

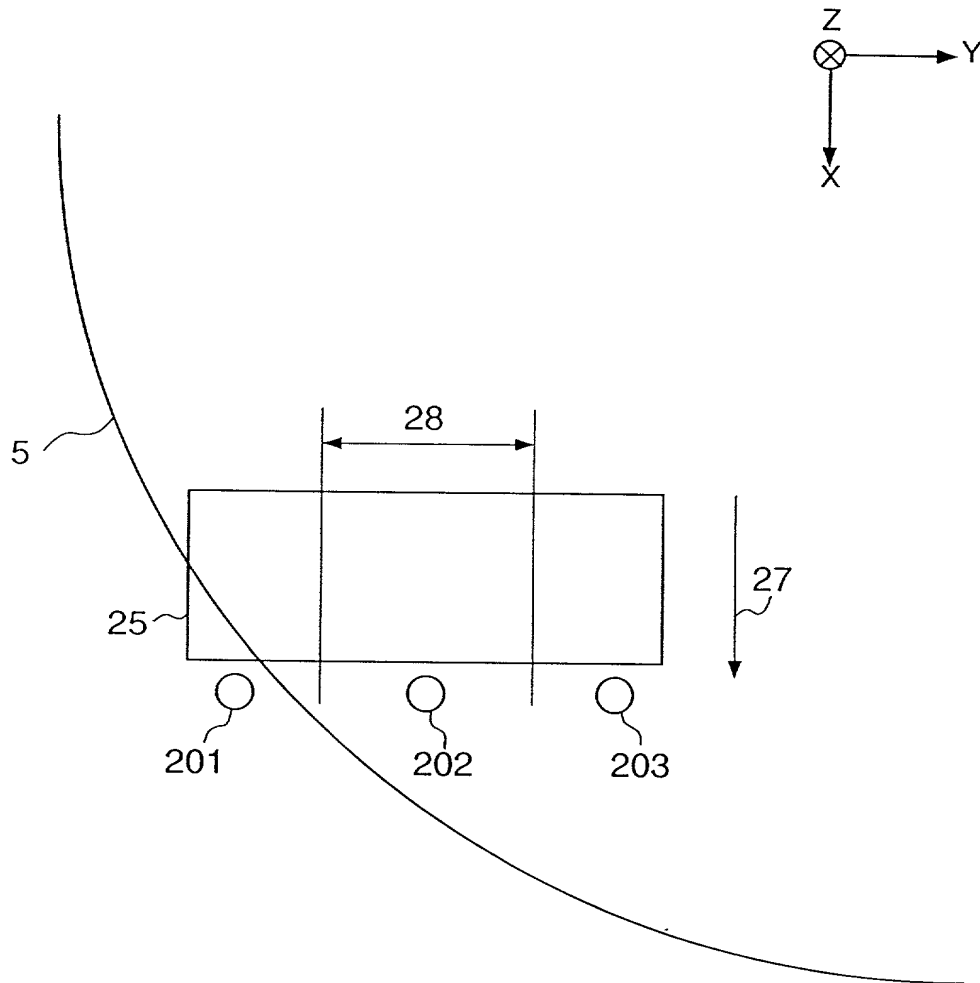
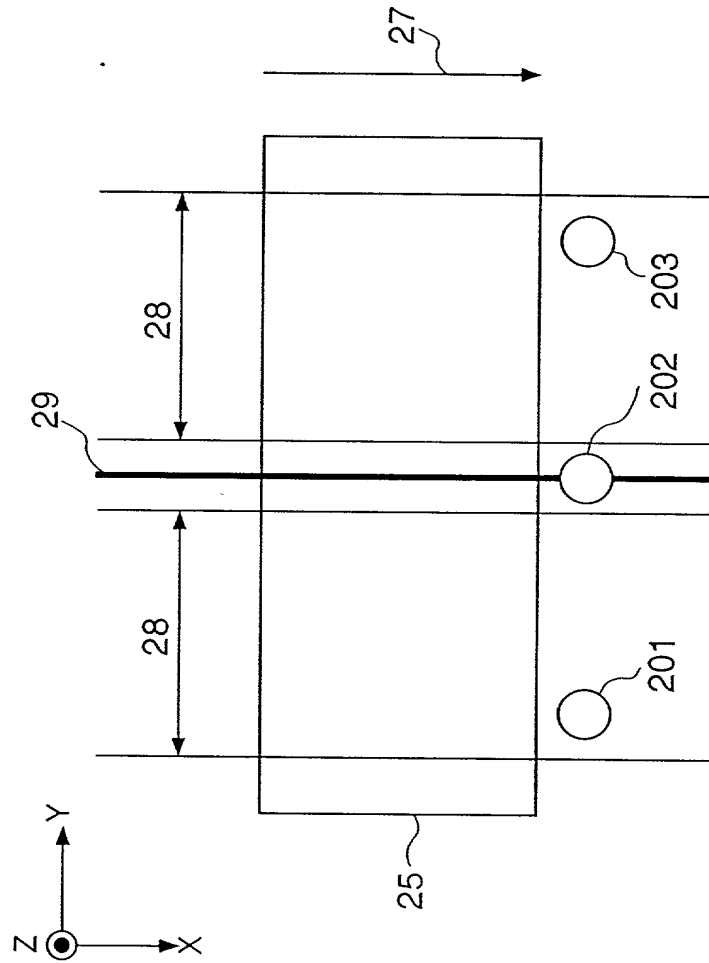




FIG. 17



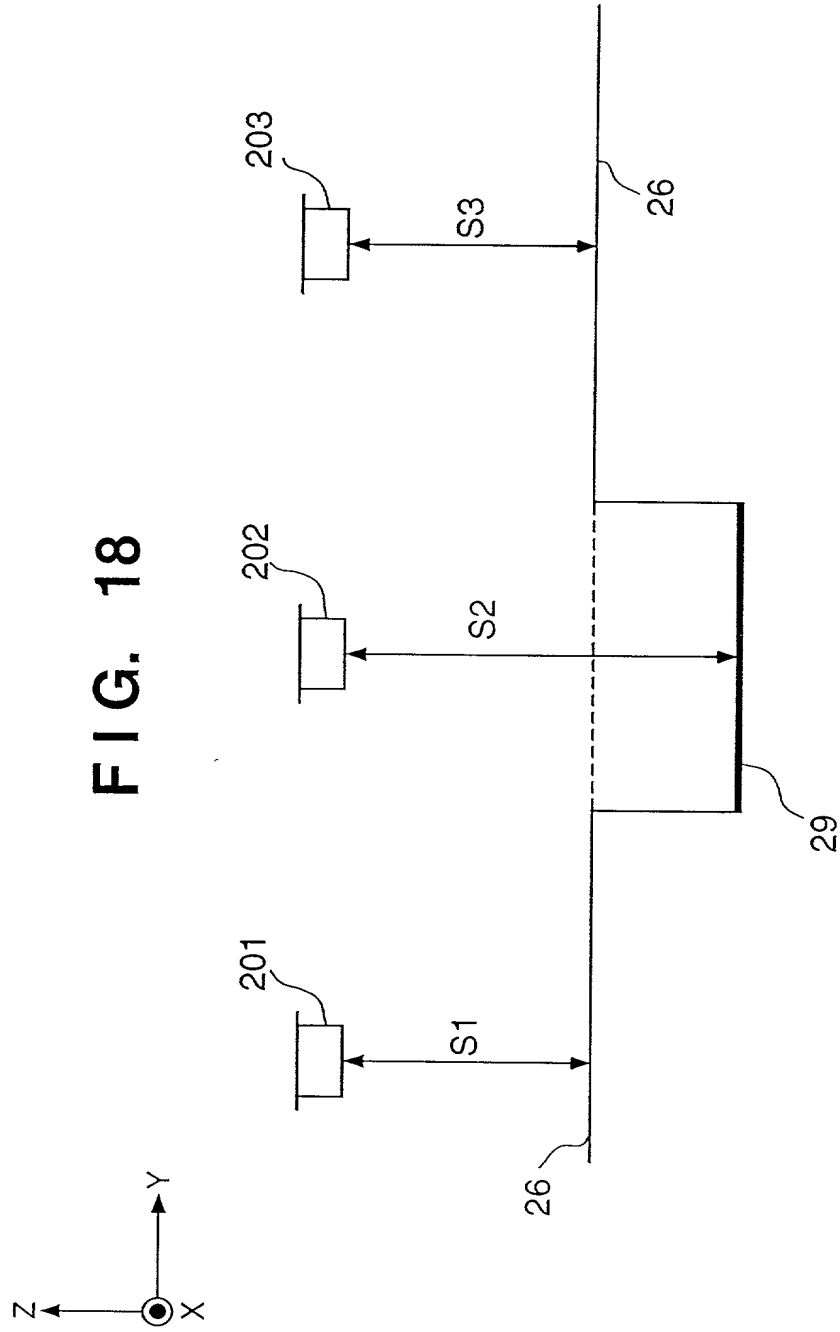


FIG. 19

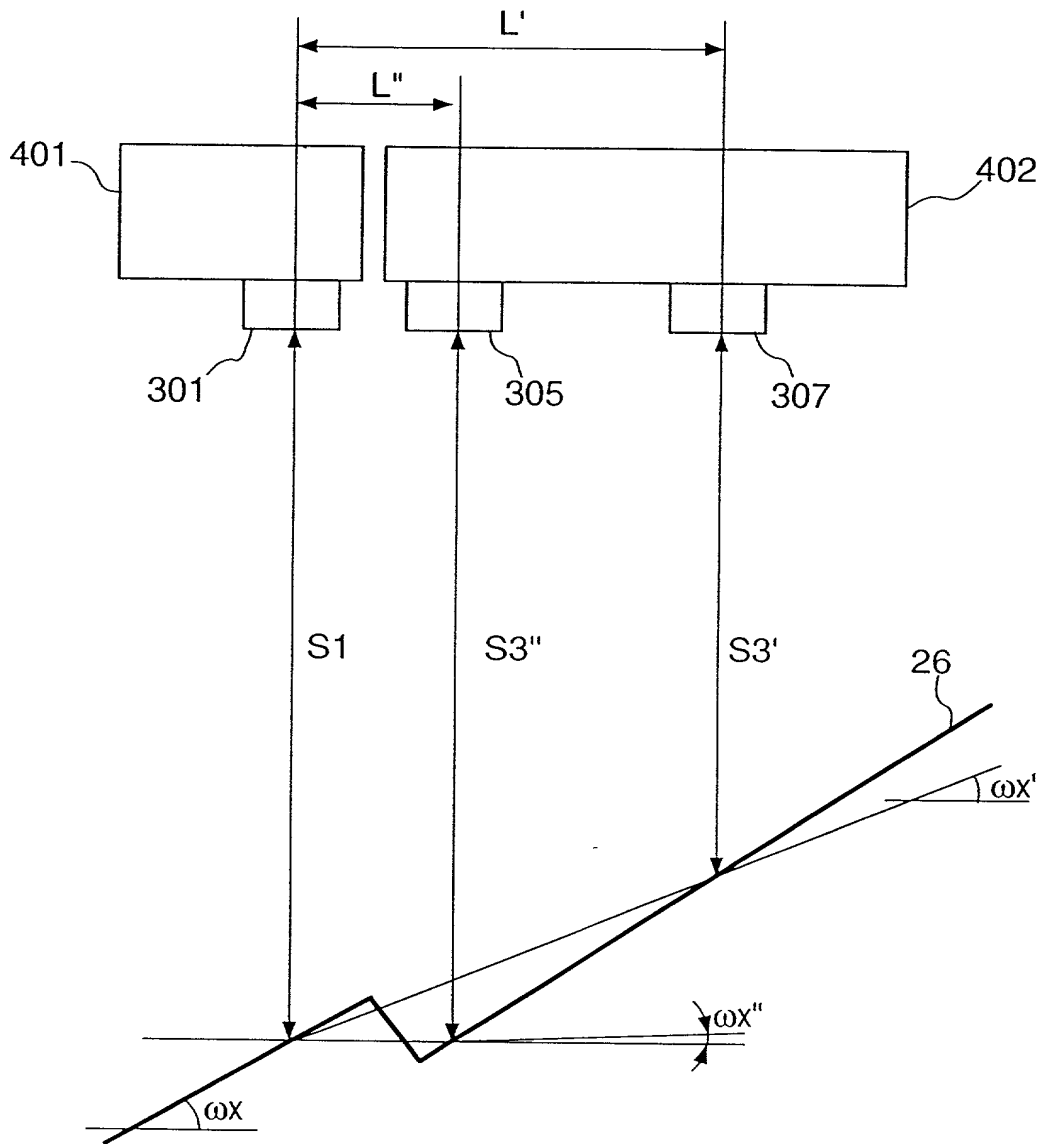
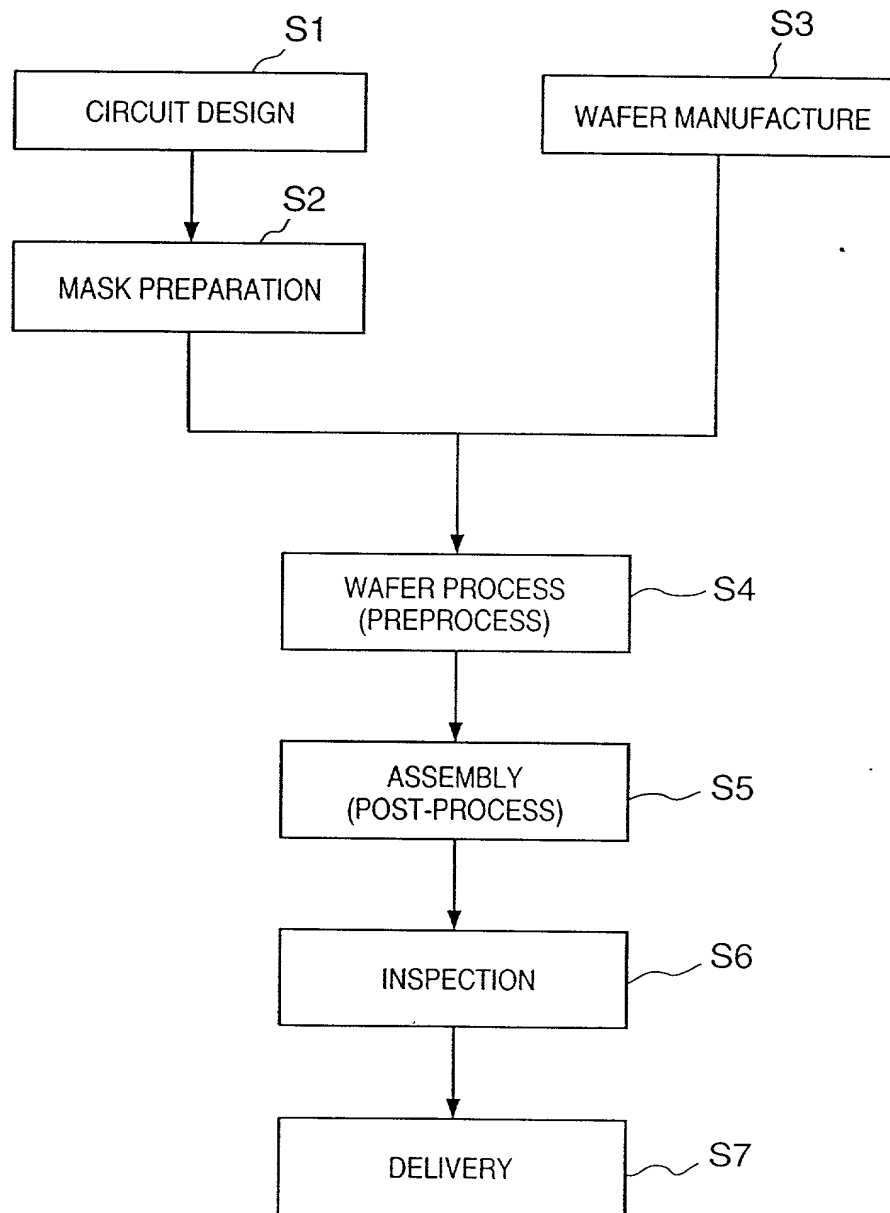




FIG. 21



SEMICONDUCTOR DEVICE MANUFACTURING FLOW

